

PLASMA ETCH PROCESS OVERVIEW

Who should attend?

This course is designed for those individuals in the semiconductor industry who require knowledge of the basic principles of the Plasma Etch Process.

Course Benefits

Introduction to process fundamentals, system components and their interrelationships.

Course Objectives

- Correctly use common terminology specific to Applied Materials and to plasma etch semiconductor processing.
- Describe what results on the wafer are important in plasma etch processing.
- Describe how plasma etch is used in a typical wafer fabrication sequence in general terms.
- Identify major etch products of Applied Materials equipment.

Course Modules

1. *Plasma Etch Process Overview*
2. *Plasma Etch Process Overview*
3. *Principles of the Etch Process*
4. *Plasma and the Etch Process*
5. *Overview of Etch Chemistry*
6. *Plasma Etch Hardware*
7. *Safety*

Registration Information

Prerequisites: *None*

Course Length: *2 hours*

Course Type: *Web-based Training*

Course Number: *TRNWEB-19*

To enroll or for more information on our products and services, please call our registrar at one of the numbers below or go to www.appliedtraining.com.

- 1-800-468-8888, option 4 (United States)
- 1-512-272-0027 (International)

Computer System Requirements:

Attending this course requires a Windows 98, NT, 2000 or XP computer using Internet Explorer 5.5 or higher. 128MB RAM or higher and high-speed Internet access is also highly recommended.